

Electronic Properties of Nitrogene/MoSe₂ Heterobilayers

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Stacking two-dimensional crystals into van der Waals heterojunctions has recently generated enormous interest because of their novel applications in high-performance photovoltaic nanomaterials. In this paper, the electronic properties of a heterobilayer constructed with nitrogene on MoSe₂, denoted as nitrogene/MoSe₂ HBL, are studied based on the first-principles calculation. It is found that the electronic band spectrum of the nitrogene/MoSe₂ HBL is simply the combination of pristine nitrogene and MoSe₂ monolayer owing to the weak van der Waals interaction. As the vertical distance decreases, the charge redistribution in the interlayer space of the heterojunctions induces a transformation from the indirect electronic band gap of the nitrogene/MoSe₂ HBL towards a direct band gap. The study of the two-dimensional ultrathin nitrogene/MoSe₂ HBL is expected to show its potential in designing and fabricating a new generation of optoelectronic devices.

topics: electronic properties, heterobilayer, van der Waals interaction, vertical distance

1. Introduction

The successful exfoliation of graphene just over a decade ago has fostered the development of two-dimensional (2D) nanomaterials. Kinds of 2D nanomaterials, such as silicene [1–4], germanene [5–7], stanene [8–10], transition-metal dichalcogenides (TMDCs) [11–15], have been proposed theoretically and experimentally as well. It is well known that the strong chemical bonds in molybdenum dichalcogenides make them rather stable with single-layer nanostructures, thus any research related has attracted enormous attention in the scientific field. The chalcogenide derivatives of molybdenum, including MoS₂ and MoSe₂, belong to the large family of layered TMDCs, which are pointed to possess intriguing electronic, optical, mechanical and chemical properties [16, 17]. In addition, the analogous 2D structure of phosphorene, known as nitrogene, is predicted to be stable with low-buckle honeycomb structure [18, 19]. The semiconductor properties of it can be modulated by biaxial tensile strain, perpendicular electric field, and monolayer stacking [19].

Heterostructures, composed of layered nanomaterials, including semimetals, insulators, semiconductors, ferromagnetic nanomaterials, superconductors, and topological insulators, have been experimentally fabricated and investigated [20–30]. The materials, referred to as van der Waals (vdW) heterostructures, reveal unusual properties and

new phenomena. For example, hybrid phosphorene/graphene heterobilayers possess tunable electronic and optical properties under external electric field [20, 21], therefore they can be used to fabricate high-speed devices. Moreover, varying the interfacial separation can effectively modulate the doping carrier concentration in hybrid heterobilayers after which the interlayer interactions are changed as well. It is reported that the band-gap and quasiparticle effective mass in a graphene/h-BN (hexagonal BN) bilayer can be effectively regulated by the in-plane homogeneous biaxial strain [22–25]. Those hybrid bilayers composed of transition-metal dichalcogenides monolayers and MXene belong to the type-II band offset [26–29] in which the conduction band minimum and valence band maximum come from different 2D materials [30]. Therefore, the investigation of a heterobilayer system is highly important for further research and possible application of 2D nanomaterials.

The excellent properties of TMDCs make them a potential substrate to support other 2D monolayers. Here, we are interested in the electronic properties of the nitrogene/MoSe₂ heterobilayer and the influence of varying the vertical distance on it. In our paper, the electronic properties of the heterobilayer constructed with nitrogene on MoSe₂ are studied based on the first-principle calculation. It is found that the electronic band spectrum of the nitrogene/MoSe₂ HBL are simply a combination of pristine nitrogene and MoSe₂ monolayer owing

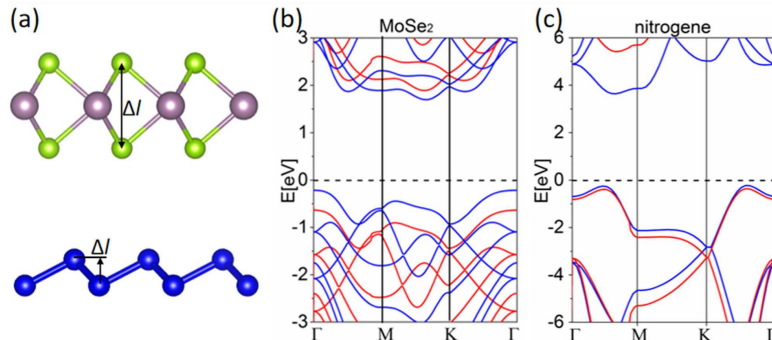


Fig. 1. The side views of MoSe₂ and nitrogen monolayer, in which the buckle height Δl is indicated (a). The purple, green, and blue balls denote, respectively, Mo, Se, and N atoms. The electronic band spectrum of the MoSe₂ (b), and the nitrogen monolayer (c), respectively, were calculated with the GGA (blue lines) and the hybrid functional HSE06 (red lines). The black dashed lines indicate the Fermi level, which has been set to zero.

to the weak vdW interaction. As the vertical distance of the heterobilayer is decreasing, the nitrogen/MoSe₂ HBL realizes a transformation from the indirect electronic band-gap semiconductor to the direct electronic band-gap semiconductor.

The next part of this paper is organized as follows: In Sect. 2, the computational details of the geometrical structures and the electronic band spectrum of MoSe₂ and the nitrogen monolayer are described. In Sect. 3, numerical results and the related discussion are given while the conclusions are provided in Sect. 4.

2. Computational method and model

All the calculations were performed based on density functional theory (DFT) as implemented in the Vienna *ab initio* simulation package (VASP) [31, 32]. The exchange-correlation function is treated within the generalized gradient approximation (GGA) and parametrized by the Perdew–Burke–Ernzerhof (PBE) formula [33]. Moreover, the electron–ion potential is described by the projected augmented wave (PAW) potential [34, 35] and a kinetic energy cutoff of 500 eV is selected for the plane wave expansion. Integrations over the first Brillouin zone are performed using the $15 \times 15 \times 1$ Monkhorst–Pack k -point grid, and 35 k -points in each high symmetry line are used to calculate the electronic bands of the hybrid nitrogen/MoSe₂ HBL. The valence electron configurations considered are Mo ($4p5s4d$), Se ($4s4p$) and N ($2s2p$), respectively. Both the lattice vectors and atomic positions are fully relaxed by minimizing the quantum mechanical stresses and forces. The convergence for energy is chosen as 10^{-5} eV between two steps and the structural optimization is obtained until the Hellmann–Feynman forces acting on each atom are less than 0.01 eV/Å. In addition, the non-bonding van der Waals interaction is incorporated by adding a semi-empirical dispersion potential to the conventional Kohn–Sham DFT

TABLE I

The lattice constants (a), bond lengths, buckle height (Δl) and band gaps (E_g) of MoSe₂ and nitrogen monolayer.

	a [Å]	Bond length [Å]	Δl [Å]	E_g [eV]	
				GGA	HSE06
nitrogen	2.29	1.50	0.70	3.89	5.78
MoSe ₂	3.32	2.54	3.34	2.08	2.52

energy, through a pairwise force field following Grimme’s DFT-D₂ method [36]. Moreover, a dipole correction is adopted to cancel the errors of electrostatic potential, atomic forces, and total energy.

The geometrical structures of MoSe₂ and a buckle nitrogen monolayer are firstly optimized in a primitive cell to determine the stable structures. The calculated parameters of MoSe₂ and the buckle nitrogen monolayers, including the lattice constants (a), the bond lengths, the buckle height (Δl) and the band gaps (E_g), are shown in Table I. As shown in Fig. 1a, the buckle height Δl of MoSe₂ is defined as the vertical distance of the upper and lower Se atoms in MoSe₂, and that of nitrogen indicates the vertical distance of N atoms in nitrogen. These results agree well with the theoretical investigations [18, 19, 37]. The electronic band spectra, calculated with the GGA and the hybrid density function HSE06 (with the same screening parameters of PBE and HF exchange), are given in Fig. 1. The band gaps of MoSe₂ and the nitrogen monolayer are, respectively, 2.08 eV and 3.89 eV for the GGA calculation. In turn, the band gaps for the HSE06 calculation are increased to 2.52 eV and 5.78 eV. As shown in Fig. 1, it is found that the hybrid density function HSE06 does not influence the spectrum trend, but only the band gaps of the monolayers are enlarged. Therefore, our numerical results are based on the GGA.

3. Numerical results and discussion

To construct the nitrogen/MoSe₂ HBLs, a commensurable supercell with 2×2 lateral periodicity of MoSe₂ and 3×3 lateral periodicity of nitrogen in the x - y plane is employed (see Fig. 2a). The lattice mismatches between the supercell of nitrogen and MoSe₂ are about 3.6%, in contrast to nitrogen, i.e., these mismatches are reasonably small in comparison with the other reported heterostructures [20–25]. Additionally, to avoid the spurious interaction between the periodic images, the vacuum region along the direction normal to the 2D plane is set to 25 Å. The vertical distance (Δh) between nitrogen and MoSe₂ is defined as the vertical distance between the lower N atoms in the nitrogen layer and the upper Se atoms in MoSe₂, as shown in the side view in Fig. 2b.

To determine the most stable geometrical structure of the nitrogen/MoSe₂ HBL, the artificial constructions of it are fully optimized from different initial structures, which are obtained by adjusting the relative position of nitrogen and MoSe₂ layers in the x - y plane. It is found that those different initial structures converge to the same geometrical structure during the geometrical optimization, in which $\Delta h = 3.43$ Å. The optimized lattice parameters of the nitrogen/MoSe₂ HBL are 6.80 Å, which is about 0.18 Å larger than the 2×2 MoSe₂ layer, and 0.08 Å smaller than the 3×3 nitrogen layer.

Our further calculations show that the influence of the little variation of the unit cell on pristine MoSe₂ and nitrogen is ignorable. In the HBL, the buckle height Δl of nitrogen is 0.70 Å, which is the same as in the case of the free-standing one.

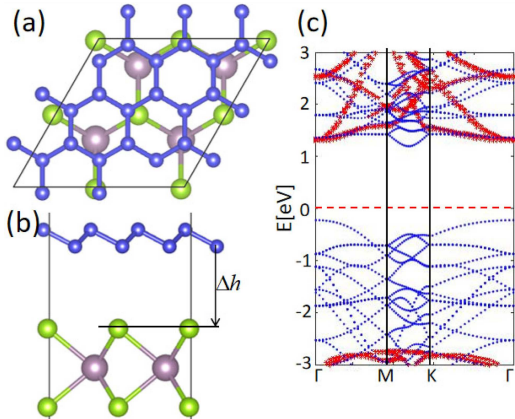


Fig. 2. The top view (a) and the side view (b) of the nitrogen/MoSe₂ HBLs, in which the optimum hybrid cells are denoted by rhombuses. The purple, green, and blue balls depict, respectively, Mo, Se, and N atoms. In the electronic band spectrum of the nitrogen/MoSe₂ HBL (c), the blue dots come mainly from the MoSe₂ layer, and the red dots are mainly contributed by the nitrogen layer. The red dashed line indicates the Fermi level, which has been set to zero.

Firstly, the formation energy is calculated to evaluate the stability of the nitrogen/MoSe₂ HBL. We use the relation

$$E_f = E_{\text{total}} - E_{\text{MoSe}_2} - E_N, \quad (1)$$

where E_{total} , E_{MoSe_2} , and E_N are the total energies, respectively, of the hybrid nitrogen/MoSe₂ HBL, pristine MoSe₂, and the buckle nitrogen monolayer. A negative E_f refers to a stable adsorption structure. The calculated formation energy of the nitrogen/MoSe₂ HBL is about -3.93 eV per supercell, which implies a stable hybrid heterostructure with van der Waals interaction.

Now, the result of calculation of the electronic band spectrum of nitrogen/MoSe₂ is shown in Fig. 2c. In the band structure, the blue circles come mainly from the MoSe₂ layer and the red stars are mainly contributed by the nitrogen layer. Owing to the weak van der Waals interaction, the hybridization between nitrogen and MoSe₂ monolayer is small. Thus, the electronic band of the nitrogen/MoSe₂ HBL is simply the combination of the electronic bands of MoSe₂ and those of the nitrogen monolayer. From the electronic band spectrum, it is seen that the valence band of the hybrid HBL is mastered both by MoSe₂ and nitrogen layers, while the conduction band is dominated by the MoSe₂ layer. Comparing with the isolated MoSe₂ and nitrogen monolayer, the conduction bands of MoSe₂ and nitrogen come closer to the Fermi level, respectively, at 1.06 eV and 1.13 eV. The conduction bands formed by nitrogen occur below the Fermi level at about -2.75 eV. In the nitrogen/MoSe₂ HBL, the band gap of the MoSe₂ layer is 1.42 eV, which is 0.66 eV smaller than the pristine MoSe₂ monolayer. In turn, the band gap of nitrogen layer is 4.07 eV, which is about 0.18 eV larger than the nitrogen monolayer. As a result, the band gap of the nitrogen/MoSe₂ HBL is 1.42 eV, which is dominated by the conduction and valence bands of the MoSe₂ layer.

To investigate the influence of spacing between nitrogen and MoSe₂ layers on the electronic properties of the nitrogen/MoSe₂ HBL, their electronic bands with different Δh are calculated. The corresponding results are provided in Fig. 3a–e, in which the red stars are mainly induced by the nitrogen layer and the blue dots come mainly from the MoSe₂ layer. It is found from the band structures in Fig. 3 that the vertical distance decreases, the integrity of the conduction band lines of the system comes closer to the Fermi level but the system's valence bands change little. As a result, the band gaps of the nitrogen/MoSe₂ HBL become smaller as the vertical distance Δh decreases. The band gaps of the nitrogen/MoSe₂ HBL varying with Δh are provided in Fig. 3f.

To properly interpret the influence of the vertical distance on the electronic behavior, the total density of states (tDOSs) of nitrogen and MoSe₂ layer in the nitrogen/MoSe₂ HBL are respectively

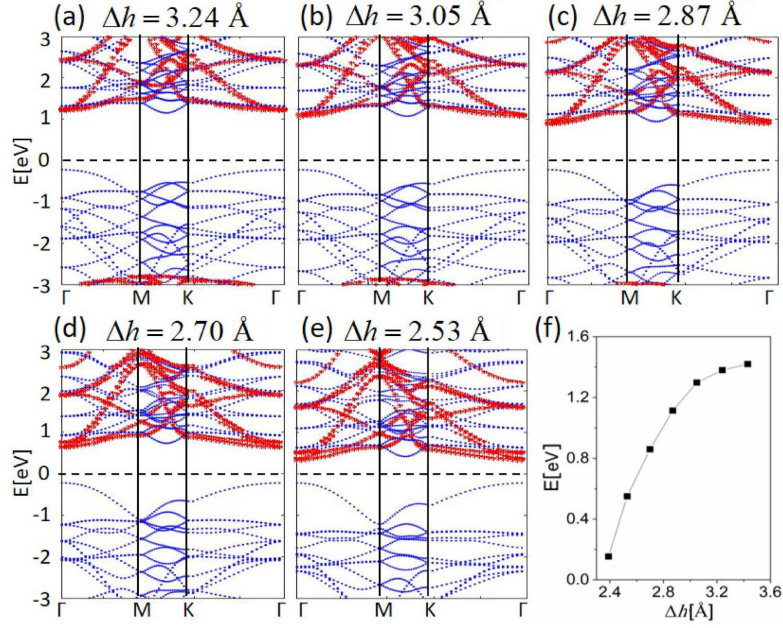


Fig. 3. The electronic band spectrum of the nitrogen/MoSe₂ HBL, respectively, with (a) $\Delta h = 3.24 \text{ \AA}$, (b) $\Delta h = 3.05 \text{ \AA}$, (c) $\Delta h = 2.87 \text{ \AA}$, (d) $\Delta h = 2.70 \text{ \AA}$, (e) $\Delta h = 2.53 \text{ \AA}$. The black dashed lines indicate the Fermi level, which has been set to zero. The blue and red dots come from MoSe₂ and nitrogen, respectively. The band gaps of the nitrogen/MoSe₂ HBL (f) vary with Δh .

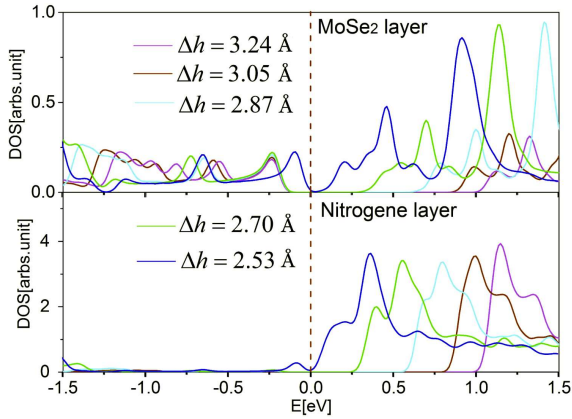


Fig. 4. The tDOSs of (a) MoSe₂ and (b) the nitrogen layer in the nitrogen/MoSe₂ HBL, respectively, with (a) $\Delta h = 3.24, 3.05, 2.87 \text{ \AA}$, (b) $2.70, 2.53 \text{ \AA}$. The red dashed lines indicate the Fermi level, which has been set to zero.

given in Fig. 4a and b. As one can see, the results are consistent with the variation of the band spectrum shown in Fig. 3a–e. On the one hand, both conduction bands of nitrogen come closer to the Fermi level to result in smaller band gaps. Such a conclusion may be drawn based on the band spectrum in Fig. 3a–e and the tDOSs in Fig. 4. On the other hand, the difference between the indirect and direct band gaps is smaller as Δh is decreasing, and the hybrid system transforms into the direct band when Δh is decreasing. For example,

at $\Delta h = 3.24 \text{ \AA}$ and $\Delta h = 3.05 \text{ \AA}$, the indirect band gaps of the nitrogen/MoSe₂ HBL are, respectively, 1.54 eV and 1.44 eV, and the direct band gaps of the nitrogen/MoSe₂ HBL are, respectively, 1.42 eV and 1.38 eV. Note that at $\Delta h = 2.87 \text{ \AA}$, the nitrogen/MoSe₂ HBL changes into direct band gap, where the direct electronic band gap is 1.11 eV.

It is known that the Se atom and the N atom manifest different electronegativities (selenium 2.55 and nitrogen 3.04), and therefore nitrogen has a deeper potential well than selenium. As a result, theoretically, when nitrogen contacts with MoSe₂, electrons tend to depart from selenium to nitrogen, resulting in an *n*-type doping of nitrogen in the nitrogen/MoSe₂ HBL. Here, to understand the charge transfer mechanism between nitrogen and MoSe₂ in the vdW HBL, the plane-integrated electron density differences are calculated according to the following equation:

$$\Delta\rho = \rho_{\text{total}} - \rho_{\text{MoSe}_2} - \rho_{\text{N}}, \quad (2)$$

where ρ_{total} , ρ_{MoSe_2} , and ρ_{N} are the plane-averaged electron densities of the nitrogen/MoSe₂ HBL, the MoSe₂ layer, and the nitrogen layer, respectively. The electron redistribution upon the formation of the interface is depicted in Fig. 5.

It is observed that there is no charge transfer between nitrogen and MoSe₂ monolayer due to the weak van der Waals interaction between nitrogen and MoSe₂ layer. However, as the vertical distance decreases, an obvious charge redistribution is observed in the interlayer space of the heterojunctions, as shown in Fig. 5. It can be seen that the charge

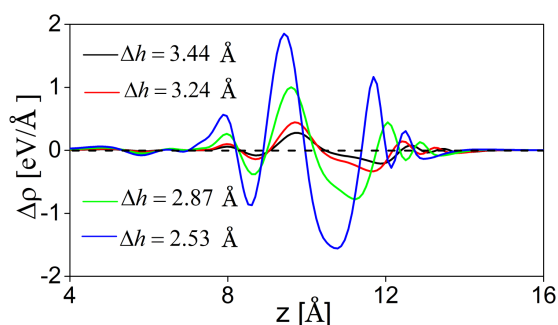


Fig. 5. Plane-integrated electron density difference of the nitrogen/MoSe₂ HBL along the vertical direction, with $\Delta h = 3.44, 3.24, 2.87,$ and 2.53 Å, respectively.

in the nitrogen/MoSe₂ HBL is gradually accumulated at the topmost Se layer of MoSe₂ monolayers. However, it is dissipated at the second Se layer of the MoSe₂ layer, resulting from the increased electrostatic interaction between nitrogen and MoSe₂ layers.

4. Conclusion

Based on the first-principle calculation, the electronic properties of the heterobilayer constructed with nitrogen on MoSe₂ are investigated. A weak van der Waals interaction between nitrogen and MoSe₂ monolayer is assumed. It is found that the electronic band spectrum of the nitrogen/MoSe₂ HBL are simply the combination of pristine nitrogen and MoSe₂ monolayer. The conduction bands are both dominated by nitrogen and MoSe₂ layers while the valence bands are mastered by the MoSe₂ layer. As the vertical distance decreases, the conduction bands come close to the Fermi level to result in a smaller indirect band gap of the nitrogen/MoSe₂ HBL. As Δh is further decreasing, e.g., at $\Delta h = 2.87$ Å, the indirect band gap transforms into the direct band gap due to the charge redistribution in the interlayer space of the heterojunctions. The study of the two-dimensional ultrathin nitrogen/MoSe₂ HBL is expected to show its potential in designing and fabricating a new generation of optoelectronic devices.

Acknowledgments

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